

REMARKS

Reconsideration of this application is respectfully requested in view of the foregoing amendment and the following remarks.

Claims 1-6 and 13-14 remain pending herein and no amendments have made to any of the claims. For the reasons stated below, Applicants respectfully submit that all claims pending in this application are in condition for allowance.

In the Office Action, claims 1, 3, and 4 were rejected under 35 U.S.C. §103(a) as being unpatentable over U.S. Patent No. 6,570,631 to Ko ("Ko"). Claims 2, 5, and 6 were rejected, respectively, under 35 U.S.C. §103(a) as being unpatentable over Ko in view of U.S. Patent Publication No. 2004/0100680 to Huibers et al., over Ko in view of U.S. Patent Application Publication No. 2005/0041182 to Ono et al., and over Ko in view of U.S. Patent No. 6,707,067 to Zhong et al. Furthermore, claims 13 and 14 were also rejected under 35 U.S.C. §103(a) as being unpatentable over Ko in view of U.S. Patent No. 5,773,848 to Wu et al. and further in view of Huibers et al. To the extent these grounds of rejection might still be applied to claims presently pending in this application, they are respectfully traversed.

Claim 1 recites that an anti-reflection layer of an anti-reflection material is disposed to contact said data line and has a same pattern as the data line for reducing reflection of a liquid crystal display. Similarly, claim 13 recites that a second anti-reflection layer of an anti-reflection material is disposed to contact a gate line and has a same pattern as the gate line for reducing reflection of the liquid crystal display.

Ko discloses a liquid crystal display comprising a first substrate (100), a data line (115) having an extension to selectively form source (121)/drains (123) of a switch, a first electrode (117), and an anti-reflection layer (134). The Examiner asserted that in Figure 4C of Ko, the anti-reflection layer (134) is shown formed on the data line (115) and, thus, concluded that the anti-reflection layer (134) is disposed to contact the data line (115) and has a same pattern as the data line (115).

However, Applicants respectfully submit that the pattern of the anti-reflection layer (134) is different from that of the data line (115), which is clearly shown in Figure 4C of Ko. Therefore, Ko needs an additional optical mask to fabricate the anti-reflection layer (134), and the excess of area of the anti-reflection layer (134) over area of the data line (115) may result in smaller aperture ratio.

In contrast, claim 1 of the application recites that the anti-reflection layer is disposed to contact the data line (drain or source) and has the same pattern as the data line. As described in paragraphs [0020]-[0022] of the specification, because the anti-reflection layer 320 is disposed on the source drain 322 and has the same pattern as the data line and the source/drain 322, no additional optical mask is needed to fabricate the anti-reflection layer 320, thereby reducing the manufacturing cost. Besides, no excess area of the anti-reflection layer is needed to cover the source/drain and the aperture ratio may be effectively raised. Accordingly, Applicants respectfully submit that claim 1 should be patentable over Ko at least due to the fact that Ko does not produce the effects and advantages of the present invention due to the disabilities of providing an anti-reflection layer of the same pattern as a data line.

As to the rejection of dependent claims 2-6 and 13-14, Applicants respectfully submit that at least due to their dependencies from patentable independent claim 1, claims 2-6 and 13-14 should be also patentable over Ko or Ko in view of any of Huibers et al., or Ono et al., or Zhong et al., or Wu et al. and Huiberts.

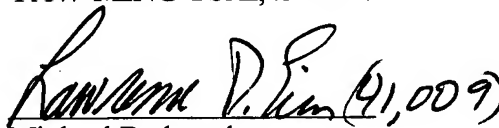
In view of the foregoing all of the claims in this case are believed to be in condition for allowance. Should the Examiner have any questions or determine that any further action is desirable to place this application in even better condition for issue, the Examiner is encouraged to telephone Applicants' undersigned representative at the number listed below.

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